

ABSTRACT

A new method is provided for the creation of a hole through a layer of insulating material. The method provides for combining a feed-forward method with a feed backward method and a high-polymer based hole profile, in order to establish a hole of a constant Critical Dimension for the hole bottom, making the CD of the hole bottom independent of the CD of the opening created through the overlying developed layer of photoresist and independent of the thickness of the layer of insulator material after CMP has been applied to the surface of the insulation layer.